


 UNIVERSITÀ DEGLI STUDI DI NAPOLI
FEDERICO II


itee^{PhD}
 information technology
 electrical engineering


DIETI

PhD Vincenzo Terracciano
 Modeling and Investigation of MPS & JBS Diodes and New
 Power Device Architectures

Tutor: Andrea Irace
 Co-Tutor: Vincenzo d'Alessandro

Cycle: XXXVIII Year: Third


 Name Surname – YEP

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My background

- MSc degree: *Electronic Engineering*
- Research laboratory: *OPTO-POWER LAB*
- PhD start date: *01/11/2022*
- Scholarship type: *ITEE*
- Partner company: *Vishay Semiconductor*


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SUMMARY OF PhD ACTIVITIES

Ad hoc PhD courses	Courses
☐ Numerical Methods For Thermal Analysis, Modeling, And simulation: Application to Electronic Devices And systems (DIETI)	☐ Numerical Models For The Fields(DIETI)
☐ Fiber Optic Sensing And Optoelectronic Circuits: Design And Application(DIETI)	☐ Analytical Mechanics (Physics Dep.)
☐ Academic Entrepreneurship (DIETI)	☐ Electrodynamics of Continuous Media (DIETI)
☐ How to boost your PhD (DIETI)	


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SUMMARY OF PhD ACTIVITIES

Contributions To Conferences	
International Conference on Silicon Carbide and Related Materials (ICSCRM), Sorrento Italy 2023,	POSTER
29 th International Workshop on Thermal Investigations of ICs and Systems (THERMINIC), Budapest Hungary 2023.	ORAL
International Conference on Silicon Carbide and Related Materials (ICSCRM), Raleigh USA 2024.	✗
European Symposium on Reliability of Electron Devices, Failure Physics and Analysis (ESREF), Parma Italy 2024.	✗
31 th International Workshop on Thermal Investigations of ICs and Systems (THERMINIC), Napoli Italy 2025.	ORAL
European Symposium on Reliability of Electron Devices, Failure Physics and Analysis (ESREF), Bordeaux France 2025.	ORAL


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SUMMARY OF PhD ACTIVITIES

THERMINIC

2025

(I 31st INTERNATIONAL Thermal Investigation)

BEST PAPER AWARD

VINCENZO TERRACCIAI

Department of Electrical Engineering and Information Technology
University of Naples Federico II, Italy & Vishay Semiconductor, Turi

FOR THE CONTRIBUTION

Electrothermal Performance Enhancement of Silicon Carbide MOSFETs
Around MOSFETs using a Ferroelectric Gate Stack

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SUMMARY OF PhD ACTIVITIES

PhD School

China-Italy Joint Laboratory on Advanced Manufacturing (CI-LAM)

Summer School Chair: Prof. Giovanni Breglio

CI-LAM

China - Italy Joint Laboratory on Advanced Manufacturing

UNIVERSITÀ DEGLI STUDI DI BERGAMO

UNIVERSITÀ DEGLI STUDI DI NAPOLI FEDERICO II

清华大学

Tsinghua University

中意先进制造联合实验室

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[1] Circuit Modelling Of SiC Merged PiN Schottky diodes

Objectives:

1. To realize a compact scalable physically electro-thermal model to describe and prevent the effect of surge current event in the SiC Merged PiN Schottky diode. The model must take into account the detrimental snapback mechanism.

2. The model should be more useful and flexible respect than standard electro-thermal TCAD simulation.

Methodology:

1. The effectiveness of the model is assessed through comparison with TCAD simulations.

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[1] Merged PiN Schottky: Structure

ANODE

Drift Region

N_D

Schottky

Substrate

CATHODE

P⁺

Drift Region

N_D

PIN

Substrate

P⁺

Drift Region

N_D

MPS

Substrate

PIN Diode Region

JBS Diode Region

Edge Termination

Ohmic contact

Schottky contact

Polyimide

SiO₂

P⁺ barrier

Space-Modulated JTE

N⁺ Drift Region

N⁺

Cathode

Current Density (A/cm²)

Forward Voltage (V)

Schottky Diode

MPS Diode

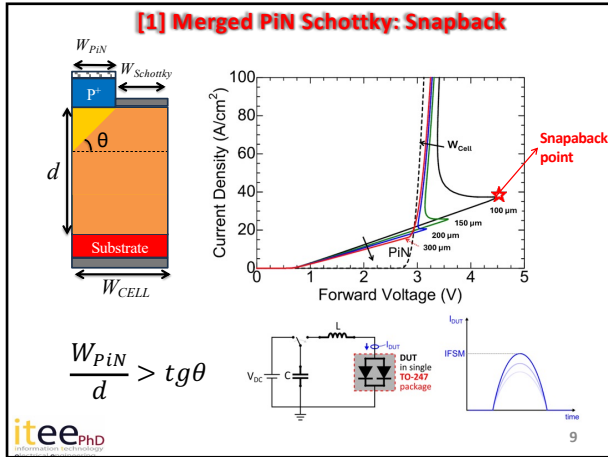
PIN Diode

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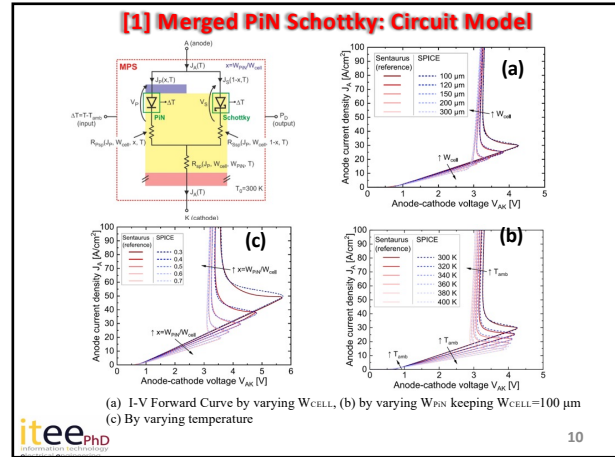
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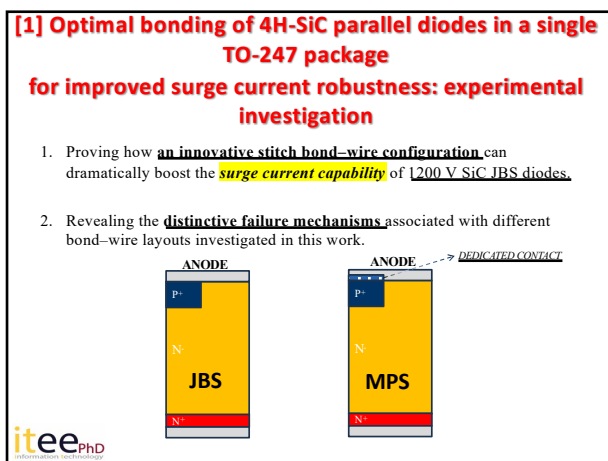
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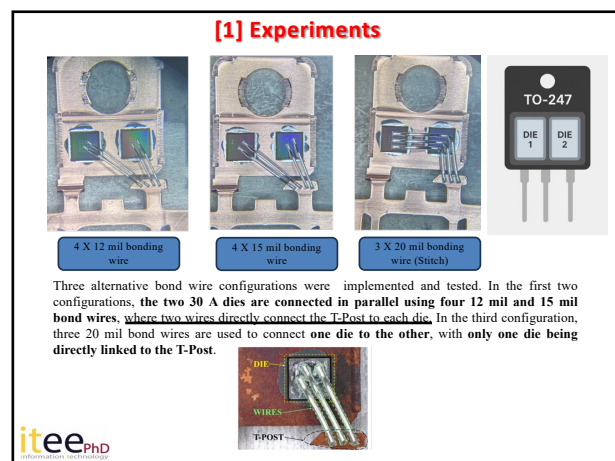
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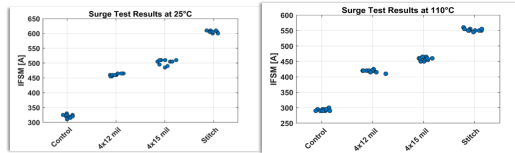


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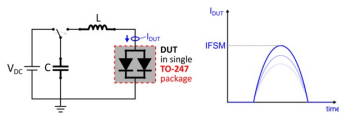


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[1] Experimental Results



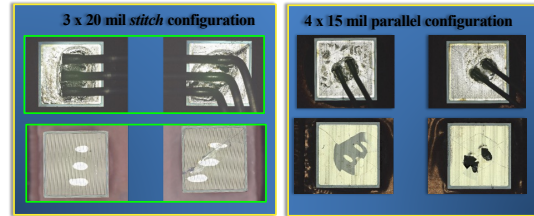
The DUTs were divided into two batches and subjected to surge current tests at 25 °C and 110 °C. Each device underwent consecutive surge pulses, with the current amplitude increasing in 5 A increments between tests.



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[1] Failure mechanism of stitch bond-wire configuration



The stitch configuration shows a asymmetrical failure mechanism respect than the parallel configurations; In practice, the stitch configuration frequently showed only the right die exhibiting visible cracks, while the left die remained intact. In contrast, in the parallel configurations, both dies were consistently cracked after the surge test

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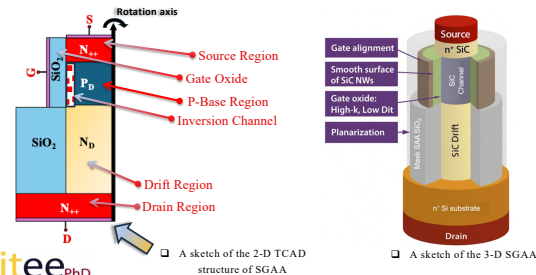
[2] SiC Gate All around MOSFETs

Objective:

Analysis and identification of design techniques for power SiC MOSFETs with gate-all-around (SGAA) architecture.

Methodology:

Study and validation of device design through TCAD simulations.

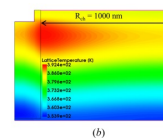
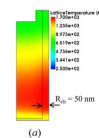


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[2] Key Properties of SiC Gate-All-Around MOSFETs

- ✓ Cylindrical Symmetry – Provides uniform electric field distribution, reducing hot spots.
- ✓ Lower Specific On-Resistance $R_{DS(on)}$ – Improved current conduction efficiency for the same chip area.
- ✓ Higher Breakdown Voltage Capability – Optimized electric field profile allows higher blocking voltages.
- ✓ Reduced Gate Charge – Enables faster switching speeds and lower switching losses.
- ✓ Low Thermal Conductivity of the surrounding oxide.



Low thermal conductivity of the surrounding oxide, combined with high current density, causes severe localized heating during short-circuit events.

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[2] Ferroelectric material integration HfO_2

□ Electro-thermal mixed-mode circuit used to simulate the short-circuit event of the devices under test (DUT)

□ Electro-thermal mixed-mode circuit parameters

- R_θ , L_{STRAT1} , L_{STRAT2} : those serve to emulate the parasitic effects of the packaging.
- R_G : internal resistance of generator
- V_{GG} : gate-connected pulse source
- V_{BUS} : supply voltage
- r_{th} : surface thermal resistance, $\left[\frac{\text{K}\cdot\text{cm}^2}{\text{W}}\right]$

□ Gate capacitance by varying temperature T

□ Drain current I_D and Max temperature T_{MAX} during short circuit

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Publications during the PhD

1. [V. Turchetta](#), A. Borghese, M. Boccarossa, V. d'Alessandro, and A. Irace, "A geometry-scalable physically-based SPICE compact model for SiC MPS diodes including the snapback mechanism," Solid State Phenomena, 2024.
2. A. Borghese, [D. Turchetta](#), M. Boccarossa, A. Irace, and V. d'Alessandro, "A geometry-scalable electrothermal compact circuit model of SiC merged-PIN-Schottky diodes accounting for the snapback mechanism: Application to current surge events," Microelectronics Reliability, 2025.
3. L. Maresca, [D. Turchetta](#), A. Borghese, M. Boccarossa, M. Riccio, G. Breglio, A. Mihaila, G. Romano, S. Wirths, L. Knoll, and A. Irace, "SiC GAA MOSFET Concept for High Power Electronics Performance Evaluation Through Advanced TCAD Simulations," Solid State Phenomena, 2024.
4. L. Maresca, [D. Turchetta](#), A. Borghese, M. Boccarossa, M. Riccio, G. Breglio, S. Wirths, and A. Irace, "Evaluation of switching performances and short-circuit capability of a 1.2 kV SiC GAA MOSFET through TCAD simulations," Key Engineering Materials, 2025.
5. V. d'Alessandro, [D. Turchetta](#), A. Borghese, M. Boccarossa, and A. Irace, "A simple electrothermal compact model for SiC MPS diodes including the snapback mechanism," International Workshop on Thermal Investigations of ICs and Systems (THERMINIC), Budapest, Hungary, 2023.
6. C. Scognamiglio, A. Borghese, K. Melnyk, I. Nistor, V. d'Alessandro, M. Boccarossa, [D. Turchetta](#), M. Riccio, A. P. Catalano, G. Breglio, N. Lophitis, M. Antoniou, M. Rahimo, A. Irace, and L. Maresca, "Out-of-SDA Performance of 3.3 kV SiC MOSFETs: Comparison Between Planar and Quasi-Planar Trench," SIE Conference, Cham, 2025.
7. [D. Turchetta](#), A. Borghese, C. Ceresa, V. d'Alessandro, and A. Irace, "Optimal bonding of 4H-SiC parallel diodes in a single TO-247 package for improved surge current robustness: experimental investigation," ESREF Conference, Bordeaux, France, 2025.
8. A. Borghese, M. Boccarossa, [D. Turchetta](#), L. Maresca, M. Riccio, and A. Irace, "Effect of the Load Inductor on the Avalanche Ruggedness of 1200-Volt Silicon Diodes during Unclamped Inductive Switching," ESREF Conference, Bordeaux, France, 2025.
9. [D. Turchetta](#), A. Borghese, M. Boccarossa, A. Irace, G. A. Salvatore, and L. Maresca, "Electrothermal performance enhancement of silicon carbide gate-all-around MOSFETs using a ferroelectric gate stack," THERMINIC Conference, Naples, Italy, 2025.

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Thank You For Your Attention

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[1] Boosting Yield: Multi-Die Integration in Power Diodes

Yield = $\frac{\text{good dice}}{N}$ N = total die count on a wafer

Yield > Yield₀

Yield₁: $\frac{\text{good dice}}{N}$ N = total die count on a wafer

Yield₂: $\frac{\text{good dice}}{N}$ N = total die count on a wafer

TO-247

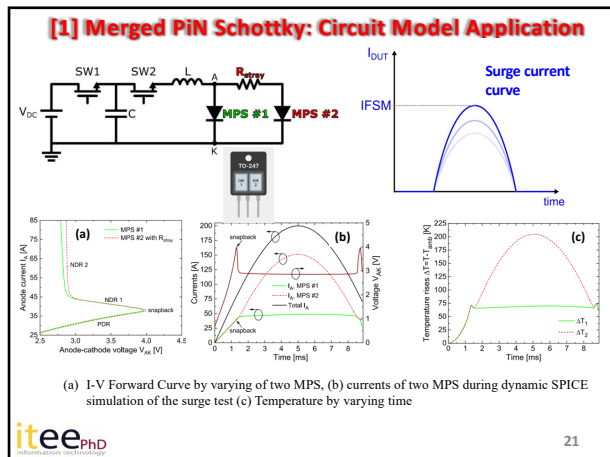
DIE 1

DIE 2

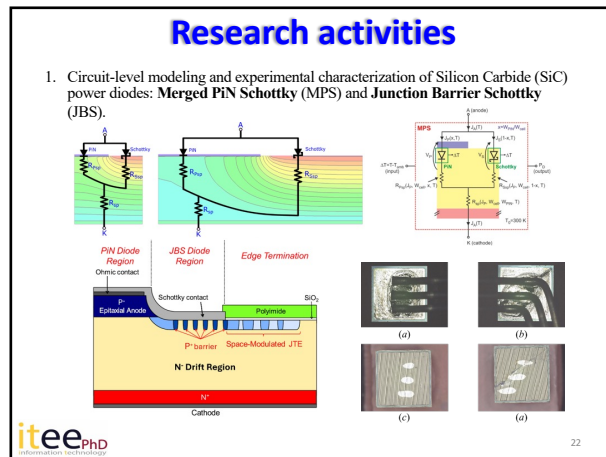
Device manufacturers commonly embed two SiC dies in parallel within the same package to increase current capability. This approach offers two key advantages: (i) it improves the fabrication process yield, and (ii) it avoids modifications to the existing semiconductor production line.

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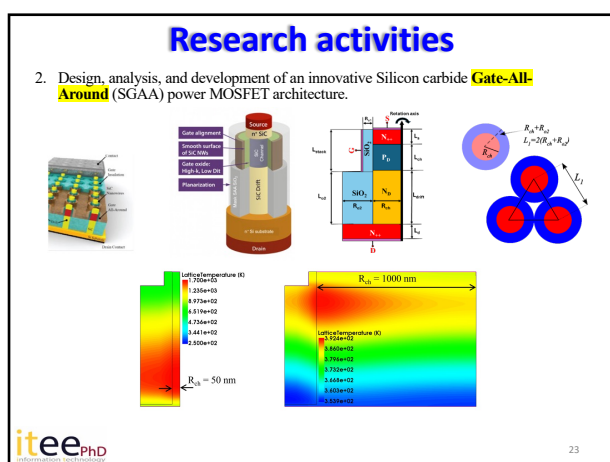
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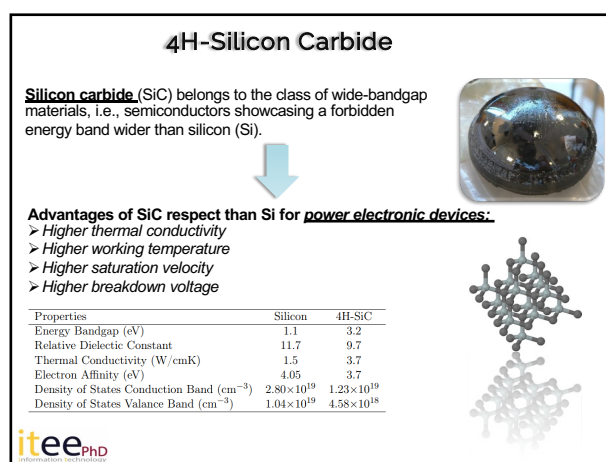
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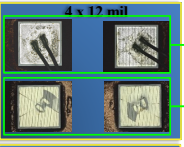
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Failure mechanism of standard bond-wire configuration

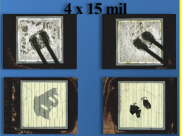
4 x 12 mil



Left and right die after chemical decapsulation

After delayering process

4 x 15 mil



Chemical Decapsulation (SiC Diodes)

❑ **Step 1 – Mold Compound Removal**

- Acid Bath with H₂SO₄, 180 °C, 5 min

❑ **Step 2 – Aluminum Delayering**

- Aqua Regia (HCl + HNO₃)

❑ **Precautions**

- Fume hood + PPE (gloves, goggles)
- Rinse with DI water between steps
- Careful time control → avoid layer damage

In the 4x12 mil and 4x15 mil configurations, both dies within the package exhibited **Failure Type 2** characteristics, including severe metal melting and structural damage. **For both configurations and at both tested temperatures (25 °C and 110 °C), the observed failure mode consistently corresponded to Type 2.**

